

Form PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Atty. Docket No. 98095DIV4	Serial No.: 10/008,653 RECEIVED JUN 25 2002 PTC 2800 MAIL ROOM
	Applicant Gonzales	
	Filing Date November 9, 2001	Group 2815



U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Patentee	Class	Sub-Class	Filing Date
h n	4,470,852	Sep. 11, 1984	Ellsworth			

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

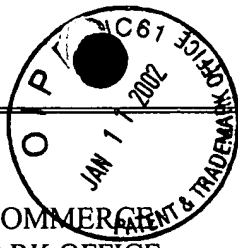
Examiner Initial	Document Number	Public. Date	County or Patent Office	Class	Sub-Class	Transl Y N

OTHER DOCUMENTS

(Including Author, Title, Date, Relevant Pages, Place of Publication)

h n	Wolf et al. (Silicon Processing For The VLSI ERA, Volume 1: Process Technology, pp. 397-399, 1986)
Examiner <i>[Signature]</i>	Date Considered 7/25/02

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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U.S. DEPARTMENT OF COMMERCE
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STATEMENT BY APPLICANT

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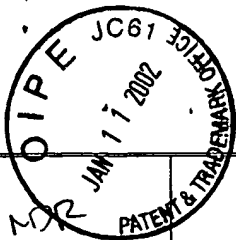
Group

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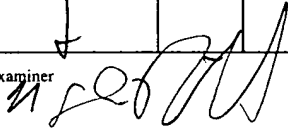
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		Moravvej-Farshi, M. et al., "Novel Self-Aligned Polysilicon-Gate MOSFETS with Polysilicon Source and Drain," Solid-State Electronics, Vol. 30, No. 10, 1987, pp. 1053-62.
		Lynch, W. et al., "UPMOS-A New Approach to Submicron VLSI," Solid State Devices, 1988.
		Yamada, T. et al., "Spread/Source Drain (SSD) MOSFET Using Selective Silicon Growth for 64mbit DRAMs," 1989 IEDM, December 3-6, 1989, pp. 35-38.
		Shin, H. et al., "MOSFET Drain Engineering Analysis for Deep Submicron Dimensions: Part II - A New Structural Approach for Deep Submicron MOSFETs," SRC, November 1991.
		M. Togo et al., "A Gate-side Air-gap Structure (GAS) to Reduce the Parasitic Capacitance in MOSFET," 1996 Symposium on VLSI Technology Digest of Technical Papers, pp. 38-39.
		Makino, T. et al., "A Stacked Source Drain MOSFET Using Selective Epitaxy," Fujitsu Limited, Publication Date Unknown.
Examiner 	Date Considered 7/25/07	
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